

*A1  
Comp*  
wherein R<sub>1</sub> is H, or a C<sub>1-30</sub> straight or branched chain alkyl, aryl, or aralkyl; and R<sub>2</sub> is COOM

wherein M is H; (CHR<sub>1</sub>)<sub>n</sub>OH; (CH<sub>2</sub>CH<sub>2</sub>O)<sub>n</sub>H; (CH<sub>2</sub>)<sub>n</sub>NR<sub>1</sub>; (CHR<sub>1</sub>CONR<sub>1</sub>H) where n is 1-100,

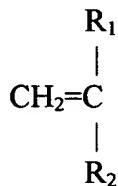
and wherein the polar monomer is present at about 2 to 29% by weight of the total polymer.

*Sub  
R2*  
17 (Amended) A two container kit for polishing nails comprising:

(a) a first container containing a nail enamel composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a film forming polymer having a glass transition temperature in the range of 5 to 90° C. obtained by polymerizing two different types of monomers wherein one monomer is a nonpolar ethylenically unsaturated monomer and the other monomer is a polar monomer of the formula:



wherein R<sub>1</sub> is H, or a C<sub>1-30</sub> straight or branched chain alkyl, aryl, or aralkyl; and R<sub>2</sub> is COOM

wherein M is H; (CHR<sub>1</sub>)<sub>n</sub>OH; (CH<sub>2</sub>CH<sub>2</sub>O)<sub>n</sub>H; (CH<sub>2</sub>)<sub>n</sub>NR<sub>1</sub>; (CHR<sub>1</sub>CONR<sub>1</sub>H) where n is 1-100,

and wherein the polar monomer is present at about 2 to 29% by weight of the total polymer; and

Sub  
B2  
cont.

(b) a second container containing a nail enamel topcoat composition comprising, by weight of the total topcoat composition:

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Cont

1-99% solvent, and

1-99% of a film forming polymer.

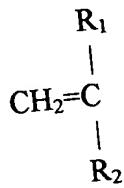
19. (Amended) A method for polishing the nails comprising:

(a) applying to the nails a first composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a film forming polymer having a glass transition temperature in the range of 5 to 90° C. obtained by polymerizing two different types of monomers wherein one monomer is a nonpolar ethylenically unsaturated monomer and the other monomer is a polar monomer of the

formula:



wherein  $R_1$  is H, or a  $C_{1-30}$  straight or branched chain alkyl, aryl, or aralkyl; and  $R_2$  is  $COOM$

wherein M is H;  $(CHR_1)_nOH$ ;  $(CH_2CH_2O)_nH$ ;  $(CH_2)_nNR_1$ ;  $(CHR_1CONR_1H)$  where n is 1-100,

and wherein the polar monomer is present at about 2 to 29% by weight of the total polymer; and

(b) applying to the nails a second composition comprising, by weight of the total composition:

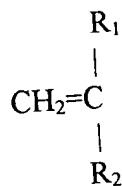
1-99% solvent, and

1-99% of an film forming polymer; wherein the dried film formed by (a) and (b) resides on the nails for five to ten days.

20. Cancel.

PLEASE ADD THE FOLLOWING NEW CLAIMS:

21. The composition of claim 1 wherein the ethylenically unsaturated nonpolar monomer is a monofunctional monomer having the formula:



wherein R<sub>1</sub> is H, a C<sub>1-30</sub> straight or branched chain alkyl, aryl, aralkyl; R<sub>2</sub> is H, CH<sub>3</sub>, a pyrrolidone, or a substituted or unsubstituted aromatic, alicyclic, or bicyclic ring where the substitutents are C<sub>1-30</sub> straight or branched chain alkyl, or COOM wherein M is a C<sub>1-30</sub> straight or branched chain alkyl, pyrrolidone, or a substituted or unsubstituted aromatic, alicyclic, or bicyclic ring where the substitutents are C<sub>1-30</sub> straight or branched chain alkyl which may be substituted with one or more halogens.

22. The composition of claim 22 wherein R<sub>1</sub> in the nonpolar monomer is H or a C<sub>1-30</sub> straight or branched chain alkyl, and R<sub>2</sub> in the nonpolar monomer is COOM wherein M is a C<sub>1-30</sub> straight or branched chain alkyl.

23. The composition of claim 22 wherein R<sub>1</sub> in the nonpolar monomer is H or methyl and R<sub>2</sub> in the nonpolar monomer is COOM wherein M is a C<sub>1-4</sub> alkyl.

24. The composition of claim 22 wherein R<sub>1</sub> is methyl and R<sub>2</sub> is COOM wherein M is butyl and the monomer is butyl methacrylate.

25. The composition of claim 24 wherein the polar monomer R<sub>1</sub> is H or methyl, and R<sub>2</sub> is COOM wherein M is H.